



PATENT APPLICATION

IN THE U.S. PATENT AND TRADEMARK OFFICE

May 14, 2008

Applicants : Yoshio KAJIYA et al

For : METHOD OF PRODUCING CATHODE MATERIAL FOR  
LITHIUM SECONDARY CELL

Serial No. : 10/521 370 Group: 1795

Confirmation No.: 2268

Filed : January 12, 2005 Examiner: Echelmeyer

International Application No.: PCT/JP2003/002027

International Filing Date : February 25, 2003

Atty. Docket No.: 4402.P0666US

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**NOTICE OF APPEAL FROM THE PRIMARY EXAMINER  
TO THE BOARD OF APPEALS**

Sir:

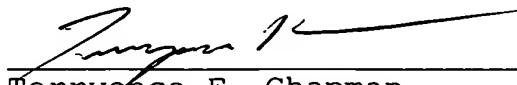
Applicant hereby appeals to the Board of Appeals from the decision mailed November 14, 2007 of the Primary Examiner finally rejecting Claims 1-8.

(Please see following page.)

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**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on May 14, 2008.

Respectfully submitted,

  
\_\_\_\_\_  
Terryence F. Chapman

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The item(s) checked below are appropriate:

A Petition and fee for extension accompany this Notice.

Appeal fee:

\$510.00 (large entity).

\$255.00 (small entity).

Statement(s) re small entity status:

Attached.

Previously filed.

A check for \$1,560.00 is enclosed to cover fees.

Please charge the Appeal Fee of \$ \_\_\_\_\_ to Deposit Account 06-1382. A duplicate copy of this sheet is enclosed.

The Commissioner is hereby authorized to charge any additional fees required by this paper or to credit any overpayment to Deposit Account No. 06-1382. A duplicate copy of this sheet is enclosed.

An acknowledgement Postal Card is enclosed.

Respectfully submitted,

IN DUPLICATE

  
Terryence F. Chapman

TFC/smd

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\*limited recognition number

Encl: Listed Above

150.09/07